



# Delta doping Technology for UV Photon Counting Detector Arrays

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KISS Single Photon Counting Detectors Workshop
California Institute of Technology
Pasadena, California

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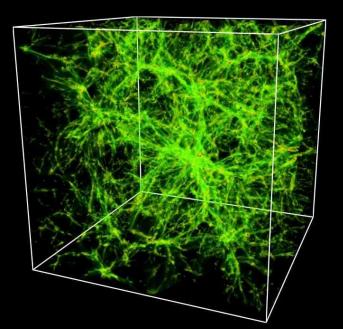
### Outline

Motivation – UV photon counting detectors

Silicon surface physics and back surface passivation

Delta-doping – nanostructured silicon by MBE

Delta-doping with high throughput and high yield



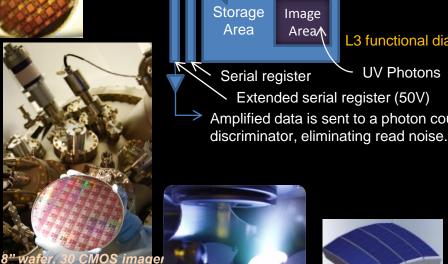
**Detector Requirement:** Six cylindrically-curved ultraviolet photon counting detector array

#### Strategy:

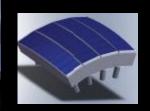
Combine delta doping with avalanche gain CCDs and AR coatings, along with Curved FPA technology

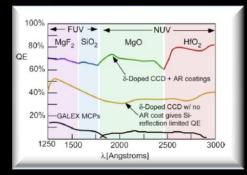
**MIDEX-ISTOS** 

PI: Chris Martin, Caltech



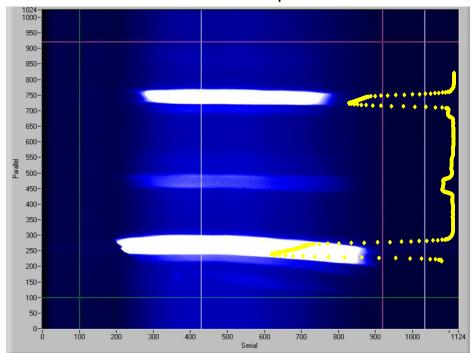
**Data Flow** Storage **Image** Area/\ L3 functional diagram **UV Photons** Serial register Extended serial register (50V) Amplified data is sent to a photon counting





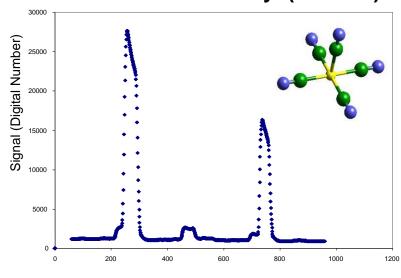
#### **Low-energy Molecular Ion Detection**

#### 5000-10000dn shown - 60s exposure /80amu centered

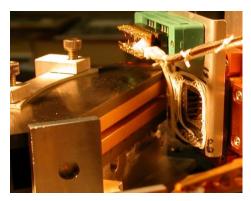


Ion Image Data - Background Image Data = Spectrum Data

#### Iron Pentacarbonyl (196amu)



**Row Number** 

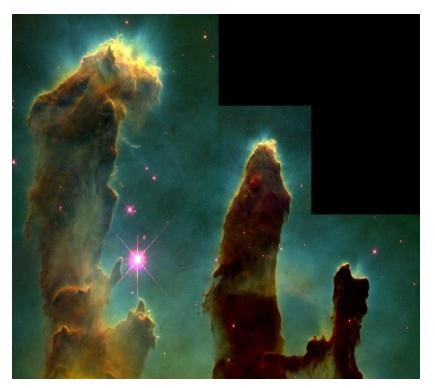


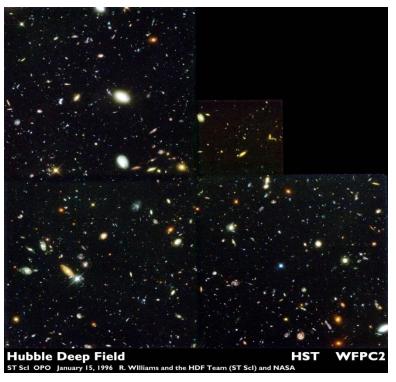
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### Silicon Imaging Arrays

"CCDs were born in the Si-SiO<sub>2</sub> revolution and created their own revolution in widespread imaging device applications."

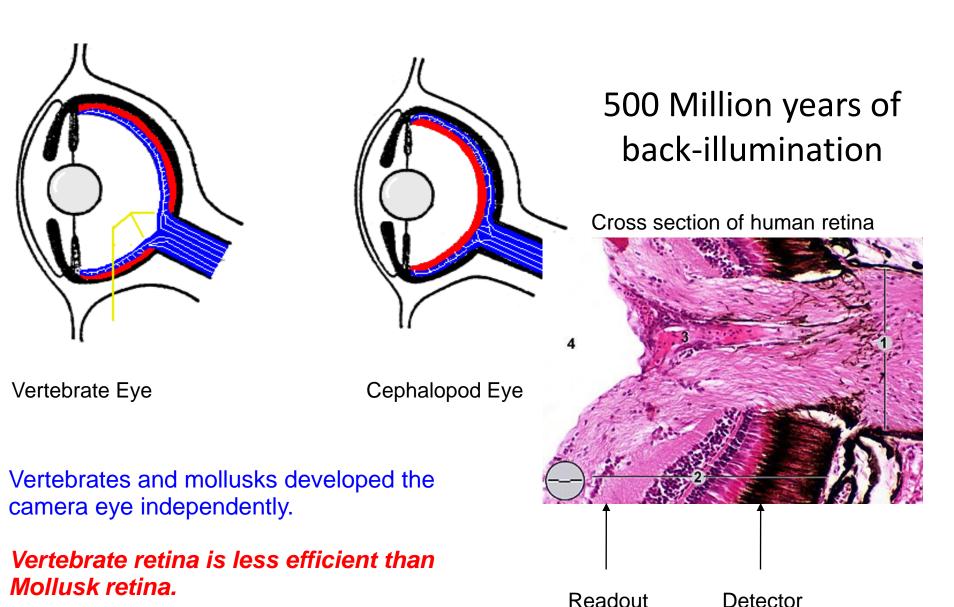
-- George Smith, co-inventor of CCDs\* and Nobel Laureate





George E. Smith, "The invention and early history of the CCD," Nuclear Instruments and Methods in Physics Research A, 607: 1-6, 2009.

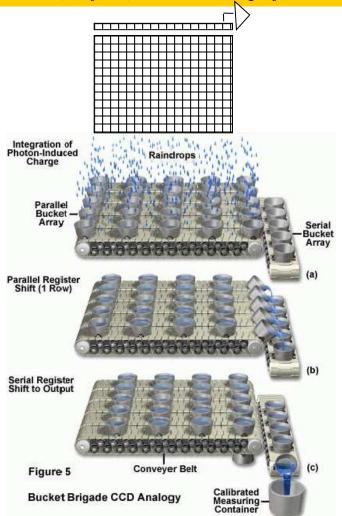
### A Brief History of Back Illumination



#### Silicon Imager Architectures: CCD vs. CMOS

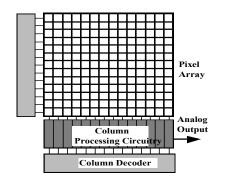
#### **Charge-coupled Device (CCD)**

Serial readout device with charge transfer and one (or few) readout amplifiers.

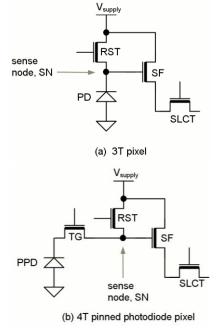


#### **CMOS Imaging Array**

Parallel readout with few charge transfers and one readout amplifier per pixel.



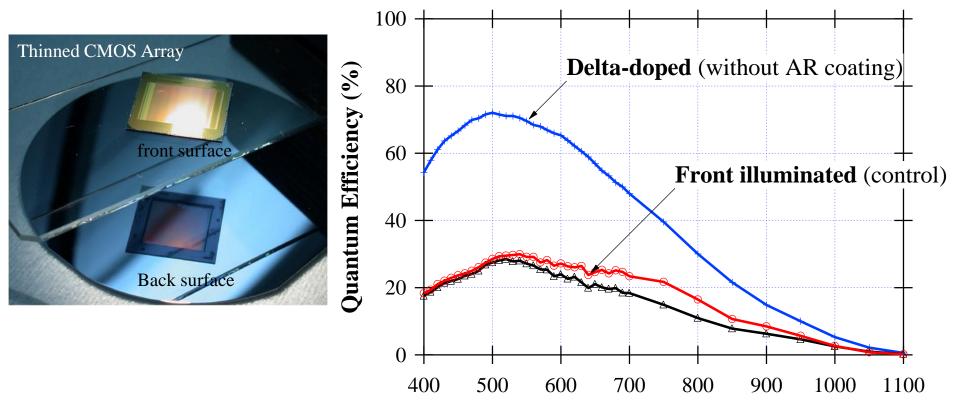
**CMOS APS** 



## Scientific CMOS imagers are catching up with CCDs

- Jim Janesick, 2009

#### **Back Illuminated CMOS Imager**

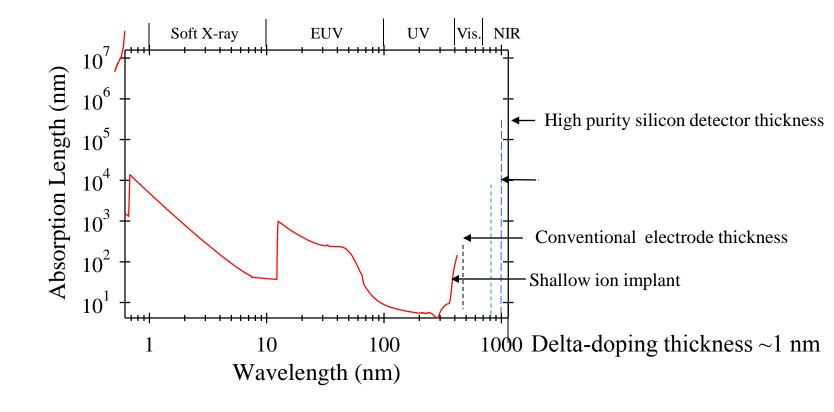


Thinning and back illumination can overcome limitations of silicon detectors:

- Quantum efficiency
- Fill factor
- Spectral range (especially in the blue-UV range)

Wavelength (nm)

### **UV Photon Absorption in Silicon**



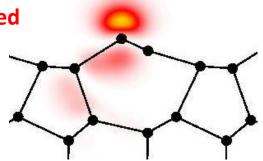
### **Between Physics and Chemistry**

#### Si-SiO<sub>2</sub> Surface States and Charging mechanisms

- Fast states / surface traps QE hysteresis
  - Acceptor-like Neutral when empty, negative when filled
  - Donor-like Positive when empty, neutral when filled
- Slow states
  - Surface charging
  - e.g., oxygen ions generated in UV flood
- Fixed oxide charge
  - Radiation damage
  - e.g., positive charge from exposure to ionizing radiation (including UV light) flattens bands

#### Surface Passivation

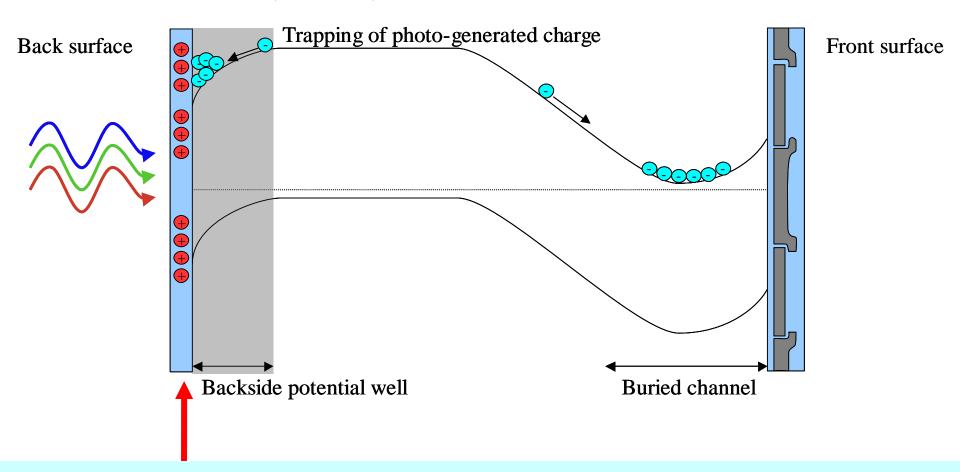
- Reduce surface state density
- Control surface potential



http://rohlfing.physik.uni-osnabrueck.de/

#### **Back Illumination and QEH**

In 1984, *quantum efficiency hysteresis* was discovered during thermal vacuum testing of Wide Field Camera (WFPC-1).



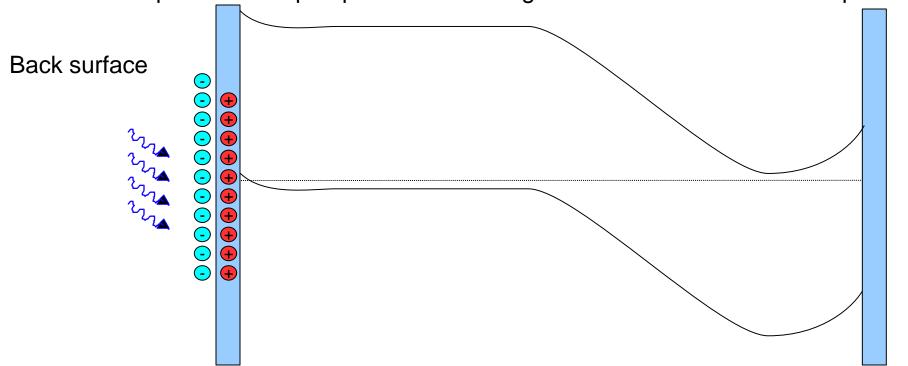
**Quantum efficiency hysteresis** – CCD response depends on prior illumination history

- Unacceptable Hubble needs stability to 1% over 30 days...
- Passivation of surface defects is necessary to solve the problem.

#### **UV Flood**

JPL developed the "UV flood" to stabilize the response (Jim Janesick and Tom Elliott).

The Hubble Space Telescope optics were redesigned to allow a "UV flood" in space.



During the mid- to late- 19800's, WFPC-1 was plagued with stability problems

To help solve this problem, JPL formed a tiger team, which included MDL scientists.

Hubble launched in 1990 with WFPC-1 on board.

NASA installed WFPC-2 in 1993, with front-illuminated, lumogen-coated CCDs.

In 1992, JPL's Microdevices Laboratory demonstrated the first delta-doped CCD.

### Quantum Efficiency Hysteresis in WF/PC 1 & 2



WF/PC1 (1983-1992) Massive UV flood at 250 nm through light pipe

WF/PC2 (1983-1992) Flash gate, biased flash gate

WF/PC2 (1992-2009) Front illuminated Loral CCDs with lumogen

John T. Trauger, "Sensors for the Hubble Space Telescope Wide Field and Planetary Cameras (1 and 2)," in *CCDs in astronomy: Proceedings of the Conference, Tucson, AZ, Sept. 6-8, 1989 (A91-45976 19-33)*, San Francisco, CA, Astronomical Society of the Pacific, 1990, p. 217-230

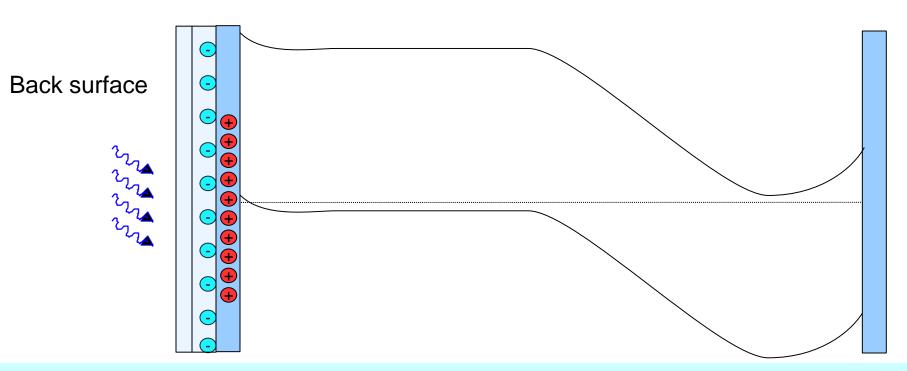
#### The Evolution of CCD Surface Passivation on Hubble

- Unpassivated
  - Doping by controlled thinning (early WF/PC 1)
- Surface charging
  - UV flood (late WF/PC 1)
  - Platinum flash gate (WF/PC 2 never flown)
  - Chemisorption charging (ACS HRC)
- Unthinned CCD
  - Front-illuminated with phosphor (WF/PC 2)
- Surface doping
  - Ion implantation (WFC3)

#### **Platinum Flash Gate**

High work function metal induces surface charge

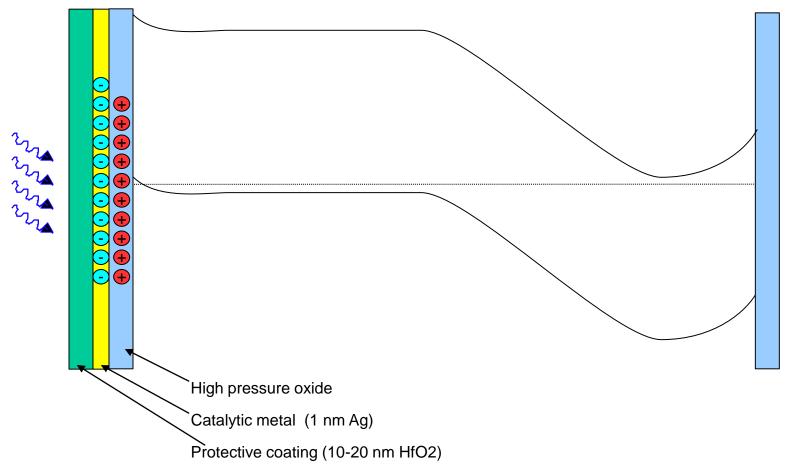
- Vulnerable to environmental contaminants (notably hydrogen)
- Encapsulation required for stability
- Passivation layer doubles as antireflection coating



Unlike MBE, surface charging methods provide poor control to environmental changes. Not suitable for high speed readout

### **Chemisorption Charging**

Metal catalyst binds  $O_2^-$  ions on the surface. Encapsulation / AR coating stabilizes the charge.



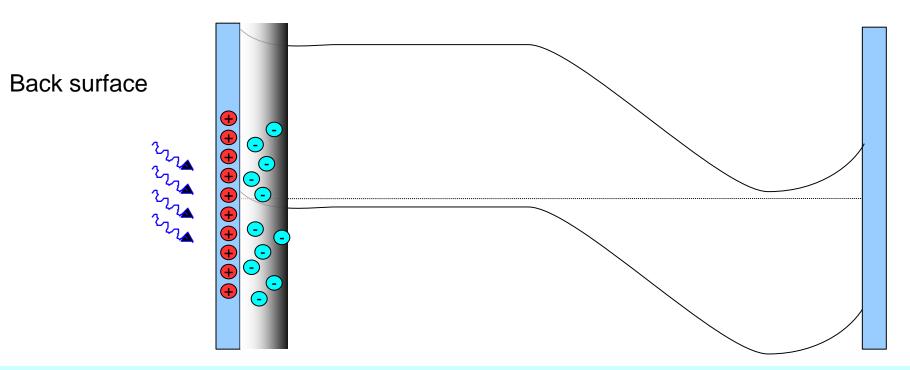
<sup>&</sup>quot;Chemisorption charging can be a permanent charging process if there are no other processes which either chemically react to remove the oxygen or contribute significant positive charge to produce a net positive charge on the surface."

—*Michael Lesser,* "CCD backside coatings optimized for 200-300 nm observations," *SPIE Proc.* **4139**: 8-15, 2000. Copyright 2010 California Institute of Technology. Government sponsorship acknowledged.

### Ion Implantation and Laser Anneal

Doping the surface introduces fixed charge into the silicon lattice

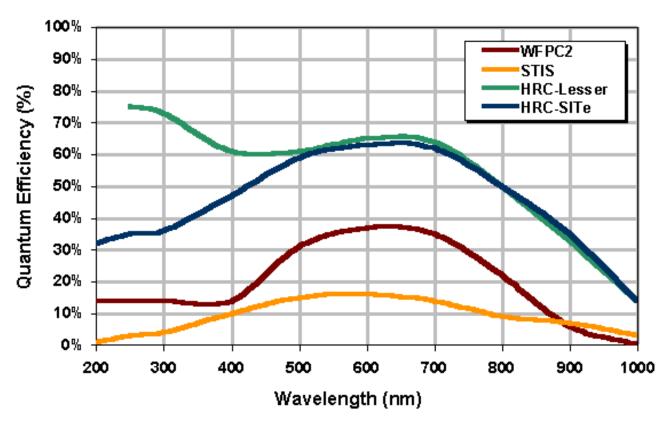
- Dopant profiles are generally broad thinner is better, but problems with traps
- Damaged lattice creates traps & dark current
- "Brick wall" pattern in flat field images from laser anneal process



Hubble's Wide Field Camera 3 uses ion-implanted CCDs.

Quantum efficiency hysteresis is still a problem.

#### The Evolution of Detector Efficiency on Hubble

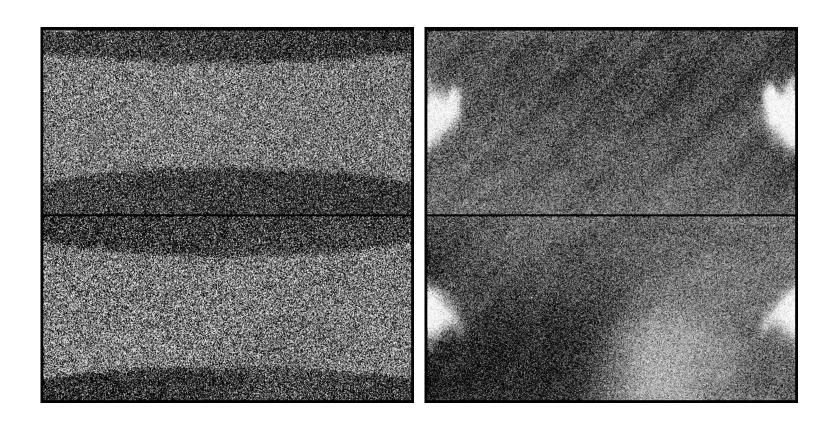


Mark Clampin, "UV-Optical CCDs", *Proceedings of the Space Astrophysics Detectors and Detector Technologies Conference*, STScI, Baltimore, June 26-29, 2000.

"The WFPC2 CCDs are *thick, front-side illuminated devices* made by Loral Aerospace. They support multi-pinned phase (MPP) operation which eliminates *quantum efficiency hysteresis*. They have a Lumogen phosphor coating to give UV sensitivity."

http://www.stsci.edu/instruments/wfpc2/Wfpc2\_hand4/ch1\_introduction2.html

### **Quantum Efficiency Hysteresis in WFC3**



#### Wide Field Camera 3

- Instabilities on the order of a few percent
- Mitigated by on-orbit flooding with visible light to fill surface traps

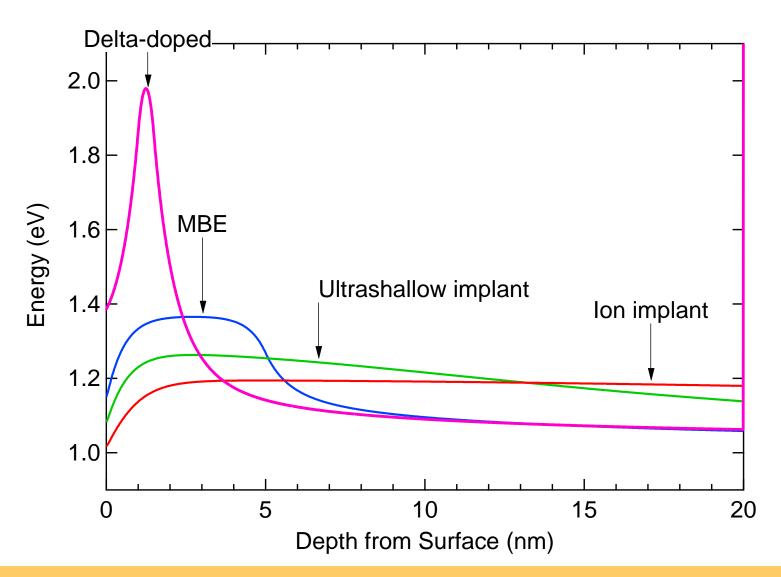
Collins et al. SPIE proceedings 7439A-10, San Diego, CA, August 2009.

### **Delta doping**

Bandstructure engineering for optimum performance Delta-doped layer Atomic layer control over device structure (dopant in single atomic layer) Low temperature process, compatible with VLSI, fully fabricated devices (CCDs, CMOS, PIN arrays) original Si Hoenk et al., Applied Physics Letters, 61: 1084 (1992) **CCD** delta-doped potential well 1.8 width  $\sim 5 \text{ Å}$ frontside circuitry Native oxide 1.6 1 nm 1.4 MBE growth  $E_{C}$ 1.2 3 nm 1.0 0.8 Back Surface Depth from surface (nm)

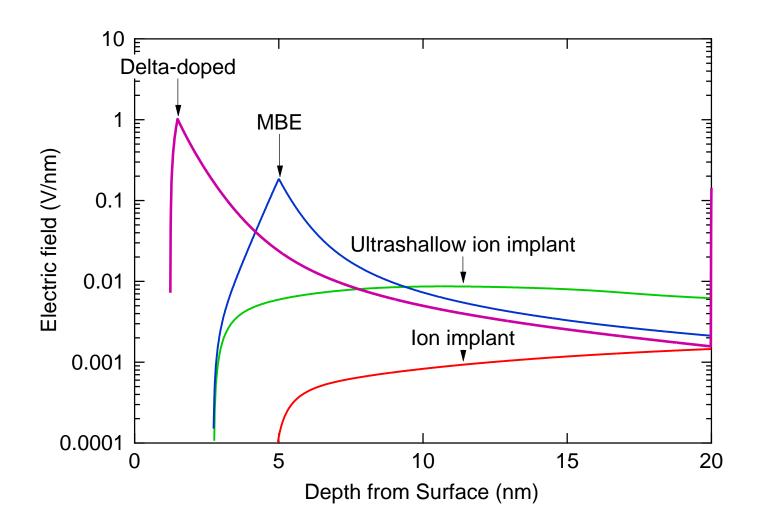
Fully-processed devices are modified using Molecular Beam Epitaxy (MBE)

### **Delta-doped Imaging Detectors**

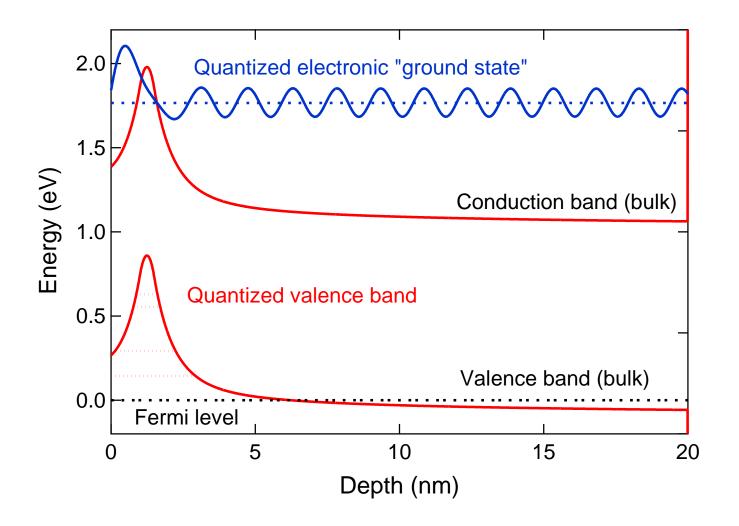


Delta doping produces ideal surface passivation in back-illuminated CCDs

### **Electric Field**



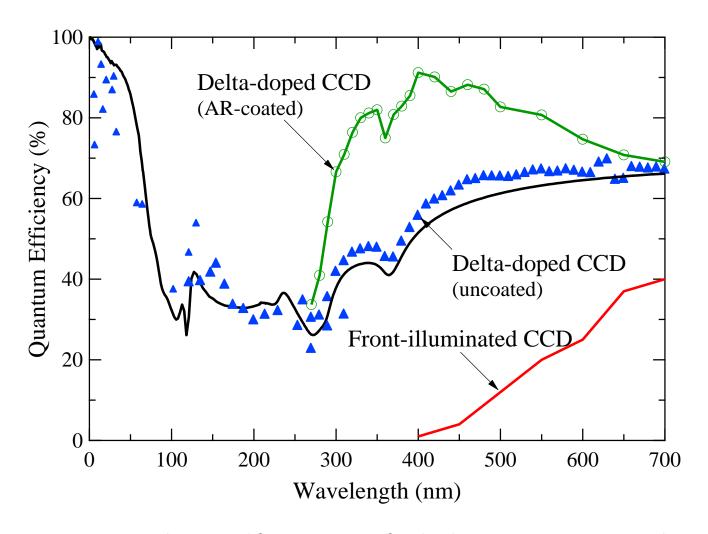
### Quantized States in Delta-doped Detectors



### Quantum Confinement in Delta-doped Surface

- Quantized states in delta-doped surface
  - Holes form 2DEG with quantized subbands
    - High conductivity surface
    - Quantum-confinement enhanced potential and fields
      - Strongly peaked potential at delta-layer
  - Electrons
    - Width of potential well ~1.5nm
    - Electrons isolated from surface by high fields
    - Quantized subbands with few quasi-bound states
- Passivation by Delta-doping
  - MBE creates abrupt interfaces, electric field ~10<sup>7</sup> V/cm
  - Buried electronic "surface" confines electrons to bulk
  - Surface dark current suppressed by quantum confinement

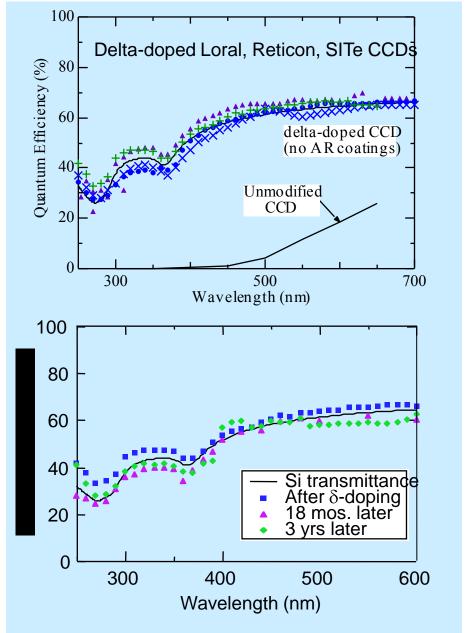
### **Quantum Efficiency of Delta-doped CCDs**



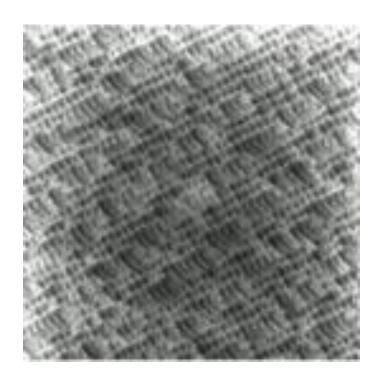
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#### **Delta-doped CCD Stability and Reproducibility**

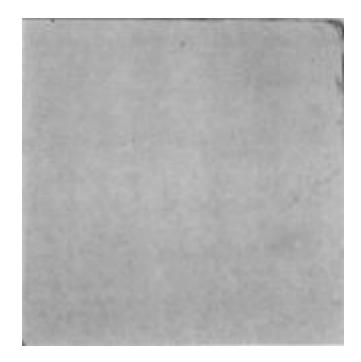
- Near 100% internal QE is measured years after the MBE modification of the CCDs
- Reproducible and compatible with different formats and CCD manufacturing processes
- No hysteresis is observed in delta-doped CCDs
- Stable response over several years
- Precision photometric stability measured by the Kepler group



### Uniformity

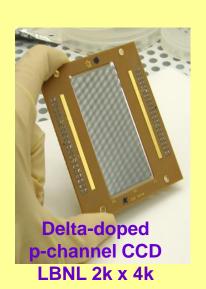


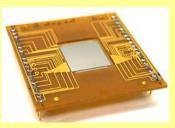
E2v CCD ion implant/laser anneal



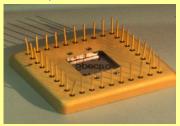
**Delta doped CCD** 

#### **Delta doped CCDs and CMOS Arrays**

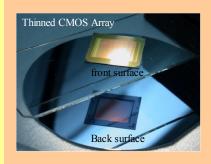


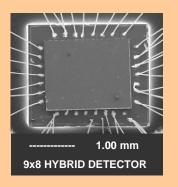


Delta-doped p-channel CCD, LBNL 1k x 1k

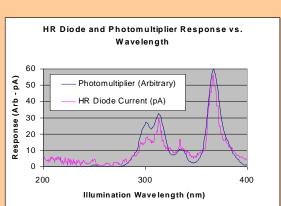


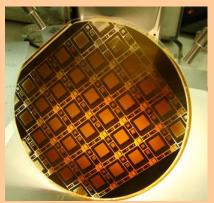
Delta-doped n-channel CCD with structurally supported membrane



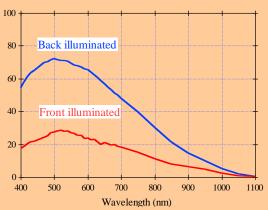


9x8 δ-doped diode array bumpbonded to APS readout

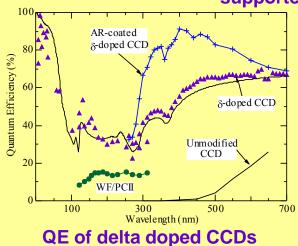




A thinned (6-µm thick) 6" wafer containing 30 CMOS devices supported by a quartz wafer.



QE of a 1kx1k delta doped CMOSAPS array



showing 100% internal QE

#### JPL Facilities for End-to-end Post-Fabrication Process



Fully-processed arrays fabricated at outside foundries are obtained.

**Bonding:** Thermocompression bonding or post MBE bonding is used for achieving flat, robust membranes



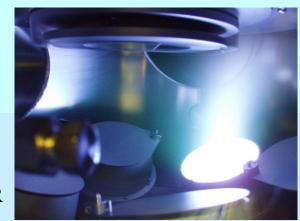
**Delta doping** MBE is used to grow a delta-doped layer of Si on the backside of fully processed silicon arrays .Response of CCD Simager is enhanced to the theoretical limit.



<u>Chemical Mechanical Polishing</u> (CMP)

Thinning: Excellent quality thinned CMOS and CCDs have been demonstrated.

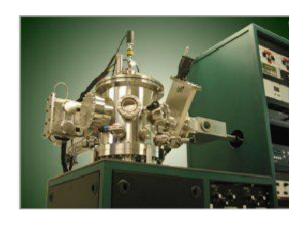
AR Coatings and Filters Modeling capability and PECVD and sputtering system for deposition of filters and AR coatings

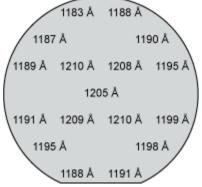


#### **AR Coating Systems**



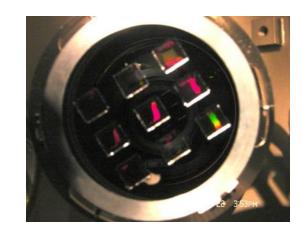




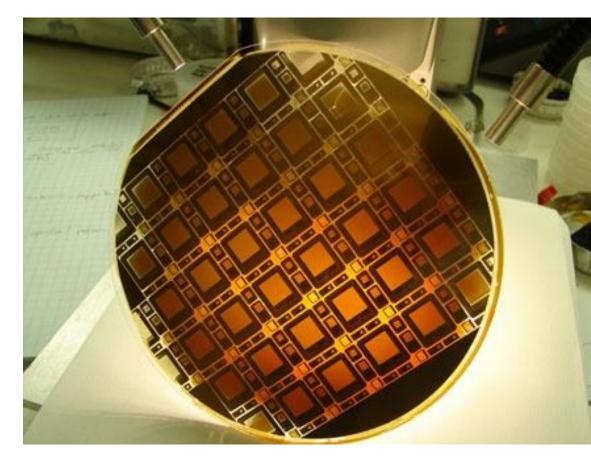




### Full Wafer Processing with 8" MBE



Raft of 9 thinned CMOS Imagers
Mounted in 3" MBE



Thinned 6" wafer with 32 CMOS Imagers

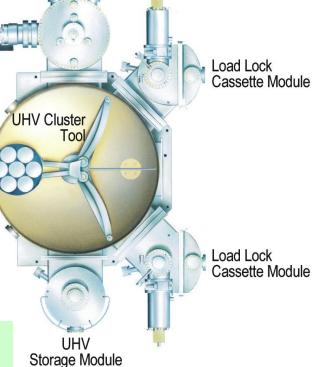
### 8-inch Wafer Silicon MBE











Preparation Module

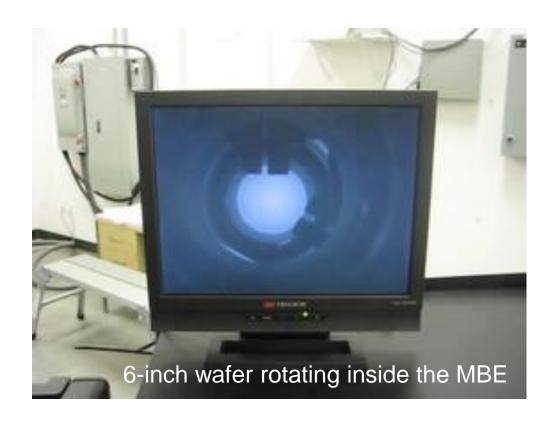
With large size wafer capacity and multiple wafer processing, high throughput processes is enabled and delta doping a lot run can be achieved in short period of time

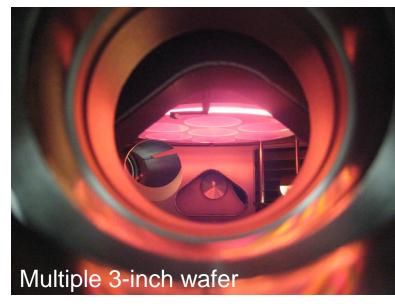


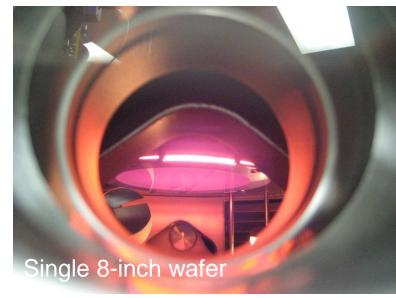
MBE after Initial Hookup at JPL

MBE under bake

### Photographs of wafers heating inside MBE







### **Conclusions**

- Delta-doped single photon detectors for UV astronomy
   ISTOS Mission: Chris Martin, David Shimonovich, Patrick Morrissey,
   Shouleh Nikzad
- Silicon surface physics and passivation Requires atomic scale control of dopant profile
- Delta-doping

Nanostructured surface by MBE Strong electric field (107 V/cm) and quantum exclusion **Proven performance** 

Future

Delta-doped L3CCDs for UV photon counting Delta-doping at wafer level for high yield and throughput